

Quantum simulations of nanoscale dual-gate FETs

Objective:

 Simulations of size-quantization effects in a novel dual-gate 2-D FET structure.

Approach:

- Three software packages namely nanoFET, nanoMOS and QuaMC 2D that are freely available on nanoHUB.org were employed.
- A double-gate SOI MOSFET with 9 nm gate length, an ultra-thin (3 nm) and intrinsic channel, and heavily doped electrodes was used as a model device.

Impact:

 nanoHUB aims at the development of new community codes that provide the nanoscience research community with new capabilities and lay a foundation for a new generation of CAD tools that will pave the way to ground breaking nanotechnology devices.

$T_{ox} = 1 \text{ nm}$ Front Gate Tsi = 3 nm $L_G = 9 \text{ nm}$ Si Channel Drain Source $L_{T} = 17 \text{ nm}$ $L_{sd} = 10 \text{ nm}$ Back Nsd = 2 x 10²⁰ cm⁻³ Gate BOX *N*_b = 0 q = 1 decade/nmSubstrate $\Phi_{G} = 4.188$ $V_{G} = 0.4 V$ E 1.E+22 2000 1.E+19 Density $V_{0} = 0.4 V$ DRAIN CURRENT [uA/um] 1 E+16 auantum Doping [1500 1.E+13 ballistic 1.E+10 1000 -⇔– nanoMOS 500 -nanoFET -∆--QuaMC 0 0.3 0.4 0.1 0.2 DRAIN VOLTAGE [V]

Result:

- The impact of quantum mechanical effects on the device properties was elucidated and key design issues were suggested.
- Availability of free and community software tools will accelerate the discovery of new and improved devices.



